NOTES:

1. SUBSTRATE: UV FUSED SILICA
2. SURFACE S2 TO BE PARALLEL WITH SURFACE S1 TO WITHIN 5 arcsec
3. COATING (APPLY ACROSS COATING APERTURE)
   S1: HARD DIELECTRIC SPUTTERED
   T(avg): ≥91% FROM 483 - 1650nm @ 0° AOI
   T(avg): ≤0.01% FROM 200 - 465nm @ 0° AOI
   T(abs): =50% FOR 475±4.75nm @ 0° AOI

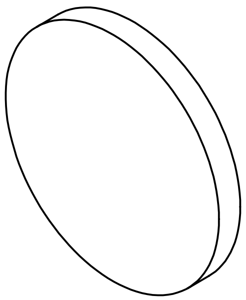
   S2:SINGLE LAYER MgF2

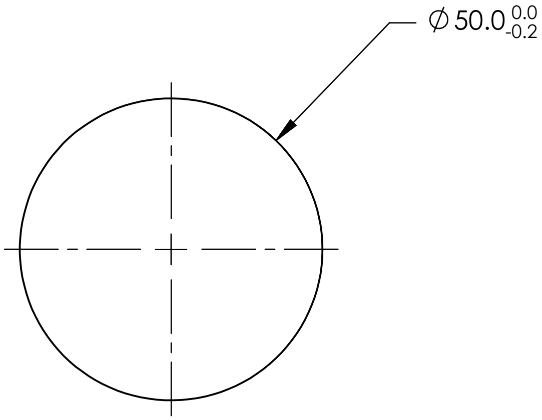
△4. FINE GRIND SURFACE

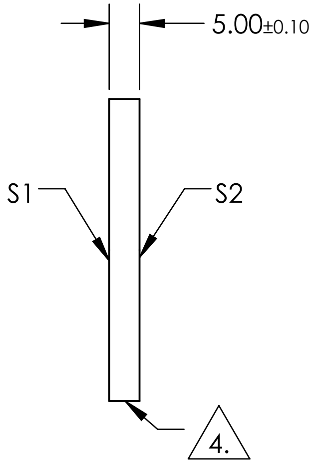
5. POWER, IRREGULARITY, AND SURFACE QUALITY SPECIFICATIONS APPLY ACROSS CLEAR APERTURE
6. TRANSMITTED WAVEFRONT DISTORTION, RMS: ≤λ/4 @ 633nm (prior to coating)
7. ROHS COMPLIANT

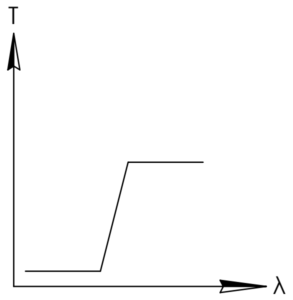
FOR INFORMATION ONLY:

DO NOT MANUFACTURE
PARTS TO THIS DRAWING









LONGPASS FILTER

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE QUALITY	60-40	60-40
CLEAR APERTURE	>80%	>80%
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

Edmund Optics®

THIRD ANGLE PROJECTION

TITLE: Ø50mm, 475nm, HIGH PERFORMANCE LONGPASS FILTER

ALL DIMS IN mm

DWG NO 84749

SHEET 1 OF 1